

PATENT *IFW*Case Docket No. **RYUKA.002AUS**

Date: September 30, 2005

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant(s) : Kouji Fujiyoshi et al.

App. No. : 10/712,594

Filed : November 12, 2003

For : ELECTRON BEAM EXPOSURE APPARATUS,
ELECTRON BEAM EXPOSING METHOD, SEMICONDUCTOR
ELEMENT MANUFACTURING METHOD, AND PATTERN
ERROR DETECTION METHOD *. O F*

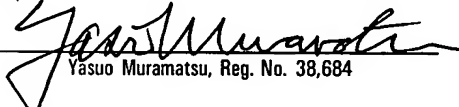
Examiner : William D. Coleman

Art Unit : 2823

I hereby certify that this correspondence and all marked attachments
are being deposited with the United States Postal Service as first
class mail in an envelope addressed to: Commissioner for Patents,
P.O. Box 1450, Alexandria, VA 22313-1450, on

September 30, 2005

(Date)


Yasuo Muramatsu, Reg. No. 38,684

TRANSMITTAL LETTER

COMMISSIONER FOR PATENTS
ALEXANDRIA, VA 22313-1450

Dear Sir:

Transmitted herewith is a response to office action in the above-identified utility application.

() An extension of time to respond for * month(s) is hereby requested.

Time Extension Fee:

- () one month (\$120 large entity)
- () two months (\$450 large entity)
- () three months (\$1020 large entity)


Enclosed are:

(X) Amendment in 28 pages.

(X) Certified copies of JP 2001-172645 and JP 2002-353141 under 35 U.S.C. 119.

(X) Return prepaid postcard.

SEND ALL CORRESPONDENCE TO:

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